

	Hits	Search Text	DBs
11	27	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same shift\$4 same (light or beam or radiation or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	5	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask or photomask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same shift\$4 same (light or beam or radiation or illuminat\$4)) and (auxilliary or serif\$3 or dummy)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
14	5	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask or photomask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same shift\$4 same (light or beam or radiation or illuminat\$4)) and (auxilliary or serif\$3 or dummy) and ((phase near14 shift\$3) or (substrate near9 groove near9 shift\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	37	((first near4 (mask or reticle or phase\$3shift\$4mask or photomask)) same ((second or third or multiple) near5 (mask or reticle or phase\$3shift\$4mask or photomask)) same (photoresist or resist or photosensitive or (radiation near5 sensitive)) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same (light or beam or radiation or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	64	((first near4 (mask or reticle or phase\$3shift\$4mask or photomask)) same ((second or third or multiple) near5 (mask or reticle or phase\$3shift\$4mask or photomask))) and ((photoresist or resist or photosensitive or (radiation near5 sensitive)) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same (light or beam or radiation or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	27	S18 NOT S17	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	15	430/394.ccls. and ((first near4 (mask or reticle or phase\$3shift\$4mask or photomask)) same ((second or third or multiple) near5 (mask or reticle or phase\$3shift\$4mask or photomask))) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same (light or beam or radiation or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	85	((first near4 (mask or reticle or phase\$3shift\$4mask or photomask)) same ((second or third or multiple) near5 (mask or reticle or phase\$3shift\$4mask or photomask))) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same (light or beam or radiation or illuminat\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	18	((first near4 (mask or reticle or phase\$3shift\$4mask or photomask)) same ((second or third or multiple) near5 (mask or reticle or phase\$3shift\$4mask or photomask))) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3) same (light or beam or radiation or illuminat\$4)) and (auxiliary or serif\$3 or dummy)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	139	((first near4 (mask or reticle or phase\$3shift\$4mask or photomask)) same ((second or third or multiple) near5 (mask or reticle or phase\$3shift\$4mask or photomask))) and (first same (mask or reticle or photomask) same second same phase same (invers\$3 or revers\$3 or shift\$4) same (light or beam or radiation or illuminat\$4)) and (auxiliary or serif\$3 or dummy)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB